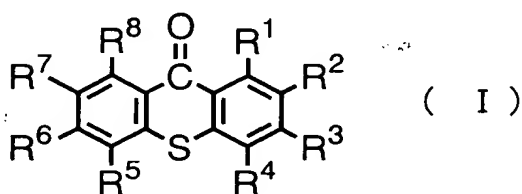


Abstract of the Disclosure

a A positive resist composition, having a superior resolution as well as good resist performances such as sensitivity, depth of focus and profile, *is described and includes* which comprises a
5 novolac resin, a radiation-sensitive quinonediazide compound and a thioxanthone compound represented by the following formula (I):



wherein R¹, R², R³, R⁴, R⁵, R⁶, R⁷ and R⁸ independently represent
10 hydrogen, halogen, alkyl, alkoxy, aryl, carboxyl or alkoxycarbonyl ~~is provided~~.